

Due: Friday, March 21, 2003

1. A  $n^+ - p$  Si junction with a long p-region has the following properties:  $N_a = 1.5 \times 10^{16} / \text{cm}^3$ ;  $\mu_n = 1020 \text{ cm}^2 / \text{V-s}$ ;  $\mu_p = 380 \text{ cm}^2 / \text{V-s}$ ;  $\tau_n = 1 \text{ } \mu\text{s}$ . If we apply 0.7 V forward bias to the junction at 300 K, what is the electric field in the p-region far from the junction? Draw a band diagram in the p-region far from the junction assuming that the junction is at  $x=0$  and the p-side is in  $x>0$ .
2. Consider the following Si p-n junctions operating at 300 K.
  - (a) Using Eq. (5-8), calculate the contact potential  $V_o$  for  $N_a = 5 \times 10^{14}$  and  $5 \times 10^{18} / \text{cm}^3$ , with  $N_d = 10^{15}, 10^{17}, 10^{19} / \text{cm}^3$  in each case and plot  $V_o$  vs.  $N_d$ .
  - (b) Plot the maximum electric field  $E_o$  vs.  $N_d$  for the junctions described in (a).
  - (c) Plot the width of the depletion region  $W$  vs.  $N_d$  for the junctions described in (a).
  - (d) Given that  $N_a = 10^{14}$  (and repeat for  $10^{19} / \text{cm}^3$ ) and  $N_d = 10^{19} / \text{cm}^3$ , determine the reverse bias needed to yield a maximum electric field  $E_o$  in the junction which exceeds  $5 \times 10^5 \text{ V/cm}$ . and what is the depletion width under the reverse biasing?
3. A  $p^+ - n$  silicon diode ( $V_o = 0.926$  volts) has a donor doping of  $10^{17} / \text{cm}^3$  and an n-region width  $= 1 \text{ } \mu\text{m}$ . Assume that the diode has a uniform cross sectional area of  $0.001 \text{ cm}^2$ . Refer to Fig. 5-22 for the following questions.
  - (a) Does it break down by avalanche or punchthrough? Determine the depletion capacitance when the breakdown happens.
  - (b) If the doping is only  $1 \times 10^{16} / \text{cm}^3$ , what is the minimum n-region width for punchthrough not to take place?